

In re Patent Application of:
COFFA ET AL.
Serial No. 10/014,880
Confirmation No. 2364
Filed: DECEMBER 11, 2001

In the Drawings

Form PTO-948 from the PTO Draftsperson refers to the drawings filed on December 11, 2001. Applicants note that revised formal drawings were filed on February 26, 2002. Accordingly, the Examiner's objection should be withdrawn.

In re Patent Application of:
COFFA ET AL.
Serial No. 10/014,880
Confirmation No. 2364
Filed: DECEMBER 11, 2001

In the Specification:

Please replace the paragraph beginning at page 8, line 7,
with the following rewritten paragraph:

--Thereafter, the trenches are sealed by depositing a silicon oxide layer, or sealant layer, by a PVAPOX process and the surface is planarized according to common techniques to produce the structure of FIG. 3c. On the so planarized surface a backplate structure of the sensor is formed according to the known technique of first depositing by a PVAPOX process a layer of sacrificial oxide 26 over the sensor area followed by the deposition of a contouring layer of silicon nitride 27 around the perimeter sacrificial oxide layer (Fig. 3d). Finally, a layer of polycrystalline silicon 28 of the backplate is deposited with a plurality of holes 30 over the sacrificial oxide layer 26 and over the perimetral layer of silicon nitride 27 as shown in FIG. 3e.--